



TL/G/10034-65

**DESCRIPTION**

Process 10 is a non-overlay, double-diffused, silicon epitaxial device. Complement to Process 68.

**APPLICATION**

This device was designed for general purpose amplifier applications at collector currents to 500 mA.

**PRINCIPAL DEVICE TYPES**

**TO-92 EBC:** PN100, PN2222

**TO-92 ECB:** 2N3415

**TO-116:** MPQ100

**TO-236:** MMBT100, 100A

**16-SOIC:** MMPQ100

**ELECTRICAL CHARACTERISTICS ( $T_A = 25^\circ\text{C}$ )**

Symbol	Conditions	Min	Typ	Max	Units
$\text{BV}_{\text{CBO}}$	$I_C = 10 \mu\text{A}$	75			V
$\text{BV}_{\text{CEO}}$	$I_C = 1 \text{ mA}$	45			V
$\text{BV}_{\text{EBO}}$	$I_E = 10 \mu\text{A}$	6			V
$I_{\text{CBO}}$	$V_{\text{CB}} = 60 \text{ V}$			50	nA
$I_{\text{CES}}$	$V_{\text{CE}} = 40 \text{ V}$			50	nA
$I_{\text{EBO}}$	$V_{\text{EB}} = 4 \text{ V}$			50	nA
$h_{\text{FE}}$	$I_C = 100 \mu\text{A}, V_{\text{CE}} = 1 \text{ V}$ $I_C = 10 \text{ mA}, V_{\text{CE}} = 1 \text{ V}$ $I_C = 100 \text{ mA}, V_{\text{CE}} = 1 \text{ V}$ $I_C = 150 \text{ mA}, V_{\text{CE}} = 5 \text{ V}$ $I_C = 300 \text{ mA}, V_{\text{CE}} = 5 \text{ V}$	80 100 100 100 60	250	600	
$V_{\text{CE(s)}}$	$I_C = 10 \text{ mA}, I_B = 1 \text{ mA}$			0.2	V
$V_{\text{BE(s)}}$	$I_C = 10 \text{ mA}, I_B = 1 \text{ mA}$			0.85	V
$V_{\text{CE(s)}}$	$I_C = 200 \text{ mA}, I_B = 20 \text{ mA}$			0.4	V
$V_{\text{BE(s)}}$	$I_C = 200 \text{ mA}, I_B = 20 \text{ mA}$			1.0	V
$C_{\text{ob}}$	$V_{\text{CB}} = 5 \text{ V}, f = 1 \text{ MHz}$		3.5	4.5	pF
$f_T$	$V_{\text{CE}} = 20 \text{ V}, I_C = 20 \text{ mA}$	200	300		MHz
$t_s$	$I_C = 10 \text{ mA}, I_{B1} = I_{B2} = 1 \text{ mA}$		275		ns
$t_{\text{OFF}}$	$I_C = 150 \text{ mA}, I_{B1} = I_{B2} = 15 \text{ mA}$		225		ns
$\text{NF}$	$I_C = 100 \mu\text{A}, V_{\text{CE}} = 5 \text{ V}, R_G = 2 \text{ k}\Omega, f = 1 \text{ kHz}$		1.5		dB
$P_{\text{D(max)}}$ TO-92 TO-236	$T_A = 25^\circ\text{C}$ $T_C = 25^\circ\text{C}$	600 350			mW mW

# Process 10

